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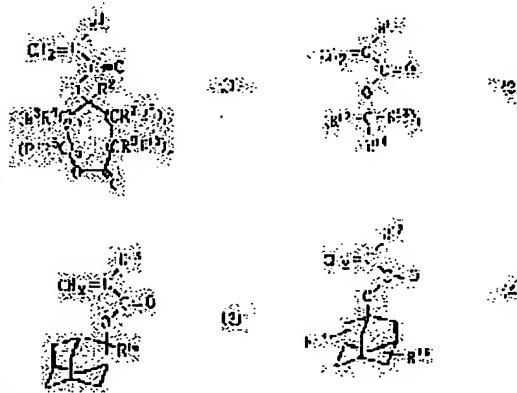
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(54) POLYMER COMPOUND FOR PHOTORESIST AND METHOD FOR PRODUCING THE COMPOUND

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a polymer compound for photoresist, containing uniformly distributed monomer units, having small intramolecular and intermolecular compositional distributions and exhibiting excellent etching resistance.

SOLUTION: The polymer compound for photoresist is produced by the copolymerization of a monomer mixture containing three kinds of (meth)acrylic acid esters comprising (A) a compound of formula 1, (B) a compound of formula 2 and/or 3 and (C) a (meth)acrylic acid ester of formula 4 having a substituted adamantane ring (R2, R12 and R13 are each H or a 1-3C hydrocarbon group; R14 is a 6-20C bridged alicyclic hydrocarbon group; R16 is methyl or the like; R18 and R19 are each H, hydroxy group, oxo group or carboxy group provided that R18 and R19 are not H at the same time; (p), (q), (r) and (s) are each 0 or 1; and p+q+r+s is 2-4).



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